Response dated February 25, 2004

Reply to Office Action dated November 26, 2003

Listing of Claims:

1. (Currently Amended) A liquid crystal display comprising:

a plurality of gate lines (GØ - Gn) formed along a first direction;

a plurality of data lines (D1 - Dn) formed along a second direction substantially perpendicular to the first direction and crossing the gate lines;

a plurality of pixel electrodes each formed in a pixel area defined by the gate lines and the data lines, the pixel electrodes indicating pictures under control of the corresponding gate lines; and

a light volume adjusting transmission restricting layer formed on a lower layer of beneath the pixel electrodes controlled by a second gate line (G1) among the gate lines.

- 2. (Currently Amended) The liquid crystal display as claimed in claim 1, wherein the light volume adjusting transmission restricting layer is an active a semiconductive layer.
- 3. (Currently Amended) The liquid crystal display as claimed in claim 2, wherein the active semiconductive layer is an amorphous silicon layer.
- 4. (Withdrawn) A method for manufacturing a liquid crystal display, the method comprising:

forming gate lines and a gate electrode on a substrate;

forming a gate insulating film on the substrate, including the gate electrode;

forming a first active layer on the gate insulating film corresponding to an upper portion of the gate electrode and forming a second active layer on the gate insulating film corresponding to a portion where pixel electrodes are to be formed;

forming source/drain electrodes on an upper portion of the first active layer; and forming a passivation film on the whole surface of the active layer including the source/drain electrodes.

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5. (Withdrawn) The method as claimed in claim 4, wherein the first and second active layers are amorphous silicon layers.

- 6. (Withdrawn) The method as claimed in claim 4, wherein a thickness of the second active layer is changed according to the transmission of light.
- 7. (Withdrawn) The method as claimed in claim 6, wherein the second active layer is adjusted in area according to an etching speed.
 - 8. (Currently Amended) A liquid crystal display (LCD) device, comprising: a substrate;
- a plurality of scanning lines (GØ Gn) extending along a first direction on the substrate;

a plurality of data lines (D1 - Dn) extending along a second direction substantially perpendicular to the first direction on the substrate and crossing the scanning lines (GØ - Gn);

a plurality of switching devices on the substrate arranged in a plurality of rows, each switching device connected to one of the scanning lines (GØ - Gn) for controlling a switching of the switching device and one of the data lines (D1 - Dn) for applying data to the switching device, wherein switching devices in each row are connected to a same scanning line, and wherein the rows of switching devices are sequentially scanned by the scanning lines (GØ - Gn);

a plurality of pixel electrodes on the substrate in a plurality of pixel areas defined by the scanning lines (GØ - Gn) and the data lines (D1 - Dn), the pixel electrodes each being connected to a corresponding one of the switching devices; and

a light transmission restricting layer formed on the substrate beneath the plurality of pixel electrodes, wherein the plurality of pixel electrodes are controlled by a second scanning line (G1) among the scanning lines (GØ - Gn).

9. (Currently Amended) The LCD device of claim 8, wherein the light transmission restricting layer is an active a semiconductive layer.

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10. (Currently Amended) The LCD device of claim 9, wherein the switching devices include a-second an active layer.

- 11. (Currently Amended) The LCD device of claim 9, wherein the active semiconductive layer is an amorphous silicon layer.
- 12. (Original) The LCD device of claim 8, further comprising an insulating material between the light transmission restricting layer and the substrate.
- 13. (Currently Amended) A method for manufacturing a liquid crystal display, the method comprising:

forming a plurality of scanning lines ($G\emptyset$ - Gn) along a first direction on a substrate; forming an insulating layer on the substrate including the scanning lines ($G\emptyset$ - Gn); forming a light transmission restricting layer on the insulating layer;

forming a plurality of data lines (D1 - Dn) along a second direction substantially perpendicular to the first direction on the substrate and crossing the scanning lines (GØ - Gn); and

forming a plurality of pixel electrodes on the substrate in a plurality of pixel areas defined by the scanning lines (GØ - Gn) and the data lines (D1 - Dn), the pixel electrodes each being controlled by one of the scanning lines,

wherein the light transmission restricting layer is formed beneath the plurality of pixel electrodes controlled by a second scanning line (G1) among the scanning lines (GØ-Gn).

- 14. (Original) The method of claim 13, further comprising forming a second insulating layer on the light transmission restricting layer before forming the pixel electrodes.
- 15. (Original) The method of claim 13, further comprising forming a plurality of switching devices on the substrate arranged in a plurality of rows, each switching device connected to one of the scanning lines (GØ Gn) and one of the data lines (D1 Dn).

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16. (Original) The method of claim 13, wherein an active layer of the switching devices is formed while forming the light transmission restricting layer.

- 17. (New) The liquid crystal display as claimed in claim 1, wherein the light transmission restricting layer is formed beneath a plurality of pixel electrodes that are controlled by a second gate line (G1) among the gate lines (GØ Gn).
- 18. (New) The method of claim 13, wherein the light transmission restricting layer is formed beneath the plurality of pixel electrodes that are controlled by a second scanning line (G1) among the scanning lines (GO Gn).